



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Atsushi Nishizawa

Serial No.: 09/751,979

Filed: 12/29/2000

MANUFACTURING METHOD OF SEMICONDUCTOR INTEGRATED CIRCUIT  
INCLUDING SIMULTANEOUS FORMATION OF VIA HOLE REACHING METAL  
WIRING AND CONCAVE GROOVE IN INTERLAYER FILM AND  
SEMICONDUCTOR INTEGRATED CIRCUIT MANUFACTURED WITH THE  
MANUFACTURING METHOD

ART UNIT: 1763

SUBMISSION OF REPLACEMENT SHEETS  
FOR FORMAL DRAWINGS

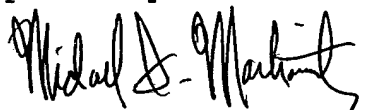
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

SIR:

Enclosed please find the replacement sheet for figures  
1 through 7c in the above referenced application.

Any fee due with this paper, not fully covered by an  
enclosed check, may be charged to Deposit Acct. No. 50-1290.

Respectfully submitted,

  
Michael I. Markowitz  
Reg. No. 30,659

Customer Number: 026304  
Telephone: (212) 940-8800  
Fax: (212) 940-8776  
Date: August 18, 2004  
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Ach: fdraw

Filed Express Mail  
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pursuant to 37 C.F.R. 1.10.  
by 